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### IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re U.S. Patent Application

Applicants:

Kurosawa et al.

Serial No.

10/612,414

Filed:

July 2, 2003

For:

THIN FILM TRANSISTOR DEVICE

METHOD OF MANUFACTURING THE SAME, ) THIN FILM TRANSISTOR SUBSTRATE AND )

DISPLAY HAVING THE SAME

Art Unit:

2826

Examiner:

Erdem, Fazli

I hereby certify that this paper is being deposited with the United States Postal Service as FIRST-CLASS mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on this date.

Date F-CLASS.WCM

Registration No. 29,367

Appr. February 20, 199

#orney for Applicant



INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir:

This IDS is submitted under 37 C.F.R. §1.97(c), after the C.F.R. §1.97(b) time period, but before the mail date of a Final Office Action or a Notice of Allowance (whichever occurs first), with either:

- (a) a statement under 37 C.F.R. §1.97(e); or
- (b) the \$180.00 fee under 37 C.F.R. §1.17(p).

Applicant(s) submit herewith Form PTO-1449 (Information Disclosure Citation) together with copies of patents, publications or other information of which applicant(s) are aware, which applicant(s) believe may be material to the examination of this application and for which there may be a duty to disclose in accordance with 37 C.F.R. §1.56. Applicant(s) respectfully submit that the citation of any reference on Form PTO-1449 does not constitute an admission that the reference qualifies as prior art.

It is requested that the information disclosed on the enclosed Form PTO-1449 be made of record in this application.

(X) Statement Under 37 C.F.R. §1.97(e):

(X) The enclosed references were cited in a Communication issued by the Taiwan Patent Office (copy enclosed). Applicant(s) hereby certify that each item of information cited on the enclosed Form PTO-1449 was first cited in any communication from a foreign patent office in a counterpart foreign application not more than three (3) months prior to the filing of this Information Disclosure Statement.

The Commissioner is hereby authorized to charge any additional fees which may be required to this application under 37 C.F.R. §§1.16-1.17, or to credit any overpayment, to Deposit Account No. 07-2069. A duplicate copy of this sheet is enclosed.

Respectfully submitted,

300 South Wacker Drive - Suite 2500

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Customer Number 24978

GREER, BURNS & CRAIN, LTD.

By:

Patrick G. Burns, Reg. No. 29,367

Form PTO-1449 U.S. Department of Commerce (Rev. 8-88) Patent and Trademark Office (INFORMATION DISCLOSURE CITATION				Attorney Docket No.: 1324.68134		Serial No.: 10/612,414		
				Applicant: Kurosawa et al.				
(Use several sheets if necessary)			Self Alex	Filing Date: 07/02/2003	Group: 2826			
U.S. PATE	ENT DOCUMENTS	PAC TRAC	EMARK			-		
Examiner Initial*	Document Number	Date	Name		Class	Subclass	Filing If Appro	
	6,225,150	May 1, 2001	Lee et al.	OIPE				
	5,055,899	Oct. 8, 1991	Wakai et al.					
	5,166,085	Nov. 24, 1992	Wakai et al.	JUN 2 1 2004 H				
•	5,877,514	Mar. 2, 1999	Seo	JUN 2 1 2004 1				
·	5,969,377	Oct. 19, 1999	Seo					
	6,225,644	May 1, 2001	Yamaguchi et al.					
					<u> </u>			
FOREIGN	PATENT DOCUMENTS					T		
							Translati	on
<b>,</b>	Document Number	Date	Country		Class	Subclass	Yes	No
	0 361 609	Apr. 4, 1990	Europe				X	
	2-224254	Sep. 6, 1990	Japan				Abs.	
	60-160170	Aug. 21, 1985	Japan		<u> </u>		Abs.	
					<u> </u>			
OTHER D	OCUMENTS (Including Aut	hor, Title, Date, Po	ertinent Pages	s, Etc.)				
						<u> </u>		
Examiner	<u> </u>	<del></del>	Date	e Considered				
*Examine	r: Initial if c	citation considered	whether or r	not citation is in conformance with	MPEP 60	09; Draw line	through o	itation
if not in conformance and not considered. Include copy of this form with next communication to applicant.								

(ENGLISH TRANSLATION)

#### OFFICIAL LETTER

Ref. No.: Chichuan No.093203463 Date of Receipt: April 22, 2004

From: THE INTELLECTUAL PROPERTY BUREAU MINISTRY OF ECONOMIC AFFAIRS

To: FUJITSU DISPLAY TECHNOLOGIES CORPORTION

c/o: PATRICK I.C. YUN AND WILLIAM W.L. CHEN, patent attorneys

SUBJECT:

It is found, upon examination of patent application no. 092118321, that clarifications in some aspects (as indicated hereunder) are still necessary. The applicant is invited to submit, in duplicate, supplementary explanation (along with any amendment) and rebuttal evidence within sixty (60) days of the day following the date of receipt of this Official Letter. This deadline cannot be extended. Failure to comply with the requirement, or a late reply to this Letter, will result in the rejection of this application.

#### **CONTENTS**:

(Translator's note: Translation of this part is omitted, since this part is concerned merely with the formality requirements for any documents to be submitted.)

If the applicant would like to have a personal interview or demonstration with the Examiner, a request therefor should be made in the Response. If deemed necessary, the time and venue for holding the interview will be arranged.

The Examiner is of the opinion that:

- 1. The invention relates to a TFT device, a method of manufacturing the same, and a display having the same.
- 2. The method of manufacturing a thin film transistor device of this invention comprises the formation of a metal layer, a gate insulation layer, a semiconductor layer and a substrate in an order from the top to the bottom, wherein the metal thin film is patterned so as to remove the metal thin film on the semiconductor layer in regions to become source and drain regions of a thin film transistor of a first conductivity type; and then the source and drain regions of the thin film transistor of the first conductivity type are formed by implanting an impurity of the first conductivity type in the semiconductor layer using the patterned metal thin film as a mask; and thereafter, the patterned metal thin film is further patterned. This invention involves the implantation of phosphorus into transistors using the patterned metal thin film as a mask, such that the transistors obtained thereby exhibit good characteristics and high reliability.
- 3. However, the technologies concerning the formation of each of the layers and the implantation in the manufacture of TFT are well known, as evidenced by US 5055899, US 5166085, US 5877514, US 5969377, US 6225150, US6225644, EP 0361609, JP A02224254 and JP A60160170. Therefore, this invention, which merely comprises the utilization of technology and knowledge existing prior to the filing date and is readily achievable by those skilled in the art, does not meet the patentability requirements. In addition, the examples given in the specification are provided with details on manufacturing the TFT without any solid data demonstrating the advantageous characteristics and reliability thereof. Thus, this invention is devoid of inventive step and does not meet the patentability requirements.
- 4. Attached hereto is copies of the cited references.

Sealed by The Intellectual Property Bureau Ministry of Economic Affairs

X06

經濟部智慧財產局專利申請案核數理由先行通知書

受 艾 备: 富士通额示线衔股份专限公司(代理 人:భ叔財 先生、陳文即 先生)

註: 查扎市松山医南京東路三投二四八號

给文日纳: 中华民团九十三年四月十九日 徐文文號: (九三)首章二(六)01058年 第0九三二〇三四六一三〇銭

主旨:第〇九二一一八三二一就弈利申請案經審查後發現尚有知說明三所述不明確之處, 司)若有具鑑反證資料或說明,請於文到次日起六十日內提出申復說明及有關反證資料一式二份 。若尼期未依通知內容辦理者,專利專實機關得依現有資料鎮行審查,請 查照。

说明:

流 7.

湖中

- 一、本案如有修正應依專利法第四十四條、第四十四條之一、第一百零二條之一、專利法施行知則第 20 二十八條及本局九十一年十一月八日智法字第〇九一八六〇〇一一八—〇號公告之規定辦理並做 修正規實新台幣一千元正(如有補充、修正就明書效圖式者,應倘具補充、修正申請書一式二份 ,並檢送補充、修正部份劃線之設明書或國式修正頁一式二价及補充、修正後無劃線之說明書或 圖式替換頁一式三份;如補充、修正後致原說明書或圖式頁數不連續者,應檢附補充、後正後之 全份說明書或團式一式三份至局)。
- 二、若希室朱局贫西示征或説明,請於中復說明實內註明「申請西詢」,本局認為有必要時,另安排 远點、時間與辦「面狗」,並徵交視實新台幣二千元正。
- 三、本案經審查認為: (一)本案「海膜電晶體装置及其製造方法,海膜電晶體基材及具有止基材之關示器」之要點在

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- 於提供一種TFT裝置,及其製造方法,與及由此TFT所製造之顯示器。
- (二)本案TFT之製造方法包括由上而下依序為金屬簿牒,問極絕緣簿膜,半導體層及基材上 ,而在金属薄膜形成圈案,以去除在銀成為第一等電型之TFT之源極與汲極區域的區域 内之半導體層上的金屬薄服,再搖由第一導電型之額質植入使用該圖案化之金屬薄照作 為草膜的半導體層内而形成該第一導電型之海膜之TFT之源極及及極區域,同時,再籍 孩已圈案化之金屬海膜形成圖案等步骤而成,而本案乃利用植入技術,使用該圖案化之 金屬海联作為單膜而將磷強干楦人,據謂可獲得良好特性及高可靠便。
- (三)惟IFT之製造方法,包括上述文各角與植入技術乃是已知之公開技術,包含US 5055899 · US 5166085 · US 5877514 · US 5969377 · US 6225150 · US 6225644 · EP 0361609 · JP A02224254、JP A60160170等,故本案係運用申請前既有之技術或知識,而為熱胃該項 技術者所能輕易完成,不舒法定專利要件。同時,本案說明實實施例只說明方法,然而 效果如何並無具體数據顯示其特性及可靠度,不具造步性 - 不符合法定事利要件。
- (四) 檢附前述引證資料循要(如附件)。

## 隔岸部都劃肝層風